The Future Made Clear



VAD-PROCESS ANHYDROUS SYNTHETIC FUSED SILICA SK-1300

SK-1300 Fused Silica

OHARA successfully developed synthetic fused silica SK-1300 as a result of significant improvements made to the conventional VAD (vapor-phase axial deposition) method of optical fiber manufacturing technology. SK-1300 is extremely high in purity and much lower in OH content thus making it the first synthetic fused silica usable in the semiconductor and liquid crystal display industries. SK-1300 is state-of-the-art in optical characteristics because it provides a high UV transmission, no micro inclusions, and solarization resistance, in addition to heat resistance, mechanical strength, and chemical resistance. These products can be used in a wide variety of industrial applications for semiconductors, optical and all physical or chemical related research featuring these applications:

1. Various devices such as TFT (poly-Si thin-film transistor LCD) and SOI (Silicon on Insulator).

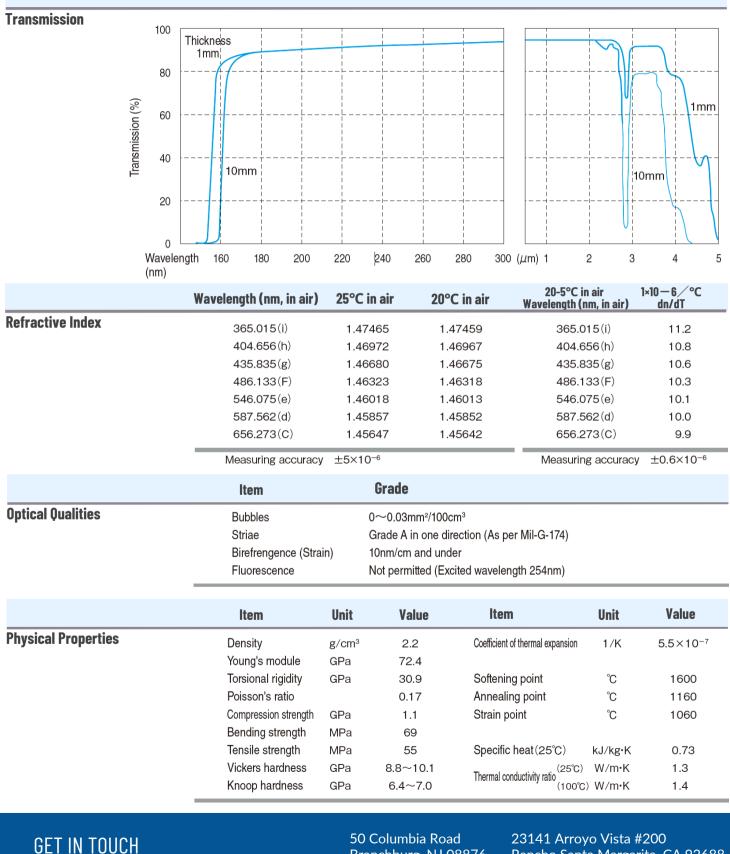
- 2. Photomask substrates for ultra-LSI and LCD.
- 3. Reactor furnace tubes, jigs and tools for ULSI manufacturing processes.
- 4. Electrical-discharge lamp tubes.

5. Optical elements, lenses, mirrors, and windows for ultraviolet and vacuum ultraviolet.

		Element	Analytical Value	Element	Analytical Value
Typical Impurity Analysis	ppb	AI	<10	Со	<10
		Fe	<10	Ni	<10
		Ti	<10	Р	<10
		Ca	<10	В	<10
		Mg	<10	Na	<10
		Mn	<10	K	<10
		Cr	<10	Li	<10
		Cu	<10	Zr	<10
	ppm	ОН	<200	CI	<1
		Solution	Treatment Temperatures (°C)	Hours	Weight Loss (mg/cm²)
Chemical Resistance)	H₂O	95	45	0.0001~0.0002
		1/100 N HNO₃	115	24	0.005~0.01
		5% NaOH	100	10	1.35

The Future Made Clear





www.oharacorp.com

Branchburg, NJ 08876 Tel: (908) 218-0100 Fax: (908) 218-1685 23141 Arroyo Vista #200 Rancho Santa Margarita, CA 92688 Tel: (949) 858-5700 Fax: (949) 858-5455